

Base models in YieldStar optics

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In this note,

I. Introduction

I.1 Test

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- [1] Mike Adel, Daniel Kandel, Vladimir Levinski, Joel Seligson and Alex Kuniavsky. *Diffraction order control in overlay metrology – a review of the roadmap options*. Metrology, Inspection, and Process Control for Microlithography XXIX, Proceedings Vol. **6922**: 692202, 2008.
- [2] Yoann Blancquaert and Christophe Dezausier. *Diffraction based overlay and image based overlay on production flow for advanced technology node*. Metrology, Inspection, and Process Control for Microlithography XXVII, Proceedings Vol. **8681**: 86812O, 2013.

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